

U.S. Department of Commerce, Patent and Trademark Office

Atty Docket No.

Application No.

M-10685-1C US

09/778,245

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant(s)

Confirmation No.

(Use several sheets if necessary)

Shing Lee et al.

9085

Filing Date

Group

February 6, 2001

2877

U.S. Patent Documents

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
HP	A1	4,039,370	8/1977	Kleinknecht			
HP	A2	4,141,780	2/1979	Kleinknecht et al.			
↑	A3	4,200,396	4/1980	Kleinknecht et al.			
	A4	4,303,341	12/1981	Kleinknecht et al.			
	A5	4,330,213	5/1982	Kleinknecht et al.			
	A6	4,408,884	10/1983	Kleinknecht et al.			
	A7	4,710,642	12/1987	McNeil			
	A8	4,790,659	12/1988	Erman et al.			
	A9	4,905,170	2/1990	Forouhi et al.			
	A10	5,164,790	11/1992	McNeil et al.			
HP	A11	5,241,369	8/1993	McNeil et al.			
HP	A12	5,329,357	7/1994	Bernoux et al.			

Foreign Patent Documents

							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
				None				

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

HP	C1	"Ultraviolet-Visible Ellipsometry for Process Control During the Etching of Submicrometer Features," N. Blayo et al., <i>J. Opt. Soc. Am. A</i> , Vol. 12, No. 3, March 1995, pp. 591-599
HP	C2	"Optical Dispersion Relations for Amorphous Semiconductors and Amorphous Dielectrics," A.R. Forouhi et al., <i>Physical Review B</i> , Vol. 34, No. 10, November 15, 1986, pp. 7018-7026
HP	C3	"Optical Properties of Crystalline Semiconductors and Dielectrics," A.R. Forouhi et al., <i>Physical Review B</i> , Vol. 38, No. 3, July 15, 1988, pp. 1865-1873

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HP	A13	5,381,233	1/1995	Chao et al.	X	X	
HP	A14	5,416,594	5/1995	Gross et al.			
HP	A15	5,607,800	3/1997	Ziger			
HP	A16	5,739,909	4/1998	Blayo et al.			
HP	A17	5,757,671	5/1998	Drevillon et al.			
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HP	A20	5,923,423	7/1999	Sawatari et al.			
HP	A21	5,956,148	9/1999	Celi			
HP	A22	5,963,329	10/1999	Conrad et al.			
HP	A23	6,031,615	2/2000	Meeks et al.			

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HP	C4	"Convergence of the Coupled-Wave Method for Metallic Lamellar Diffraction Gratings," L. Li et al., <i>Journal of the Optical Society of America A</i> , Vol. 10, No. 6, June 1993, pp. 1184-1188
HP	C5	"Multi-layer Modal Method for Diffraction Gratings of Arbitrary Profile, Depth, and Permittivity," L. Li, <i>Journal of the Optical Society of America A</i> , Vol. 10, No. 12, December 1993, pp. 2581-2591
HP	C6	"Optical Characterization of Amorphous and Polycrystalline Silicon Films," E. Ibok et al., <i>Solid State Technology</i> , August 1995

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HP	A24	6,118,525	9/2000	Fossey et al.		
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HP	A27	09/833,084	4/10/01	Abdulhalim et al.		
HP	A28	09/742,029	12/20/00	Zhao et al.		
HP	A29	09/741,663	12/19/00	Shchegrov et al.		
HP	A30	09/639,495	8/14/00	Nikoonahad et al.		
HP	A31	09/697,025	10/26/00	Nikoonahad et al.		
HP	A32	09/671,715	9/27/00	Fabrikant et al.		

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HP	C7	"Metrology of Subwavelength Photoresist Gratings Using Optical Scatterometry," C.J. Raymond et al., <i>J. Vac. Sci. Technol. B</i> , Vol. 13, No. 4, Jul/Aug 1995, pp. 1484-1495
HP	C8	"Linesize Effects on Ultraviolet Reflectance Spectra," D.H. Ziger et al., <i>Opt. Eng.</i> , Vol. 36, No. 1, January 1997, pp. 243,-250
HP	C9	"A Modal Analysis of Lamellar Diffraction Gratings in a Conical Mountings," L. Li, <i>Journal of Modern Optics</i> , Vol. 40, No. 4, 1993, pp. 553-573

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				<i>none</i>			
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
<i>178</i>	C10	"A Broadband UV Small Spot Spectroscopic Ellipsometer," T.R. Corle, <i>SPIE Microlithography</i> , 1995, pp. 1-12.					
<i>178</i>	C11	"Rigorous Coupled-Wave Analysis of Planar-Grating Diffraction," M.G. Moharam et al., <i>J. Opt. Soc. Am.</i> , Vol. 71, No. 7, July 1981, pp. 881-818.					
<i>178</i>	C12	"Scatterometry and the Simulation of Diffraction-Based Metrology," S. Sohail et al., <i>Microlithography World</i> , Jul/Aug/Sep 1993, pp. 5-16					
<i>178</i>	C13	"Analysis and Applications of Optical Diffraction by Gratings," T.K. Gaylord et al., <i>Proceedings of the IEEE</i> , Vol. 73, No. 5, May 1985, pp. 894-937.					
<i>178</i>	C14	"Stable Implementation of the Rigorous Coupled-Wave Analysis for Surface-Relief Gratings: Enhanced Transmittance Matrix Approach," M.G. Moharam et al., <i>J. Opt. Soc. Am. A</i> , Vol. 12, No. 5, May 1995, pp. 1077-1086.					
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